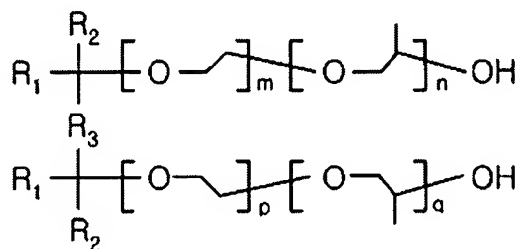


# CLEANING SOLUTION USED IN PROCESS OF FABRICATING SEMICONDUCTOR DEVICE

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## ABSTRACT OF THE DISCLOSURE

A cleaning solution used in processes of fabricating semiconductor devices is disclosed. The cleaning solution includes deionized water and a surfactant represented by the following formula:



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wherein  $\text{R}_1$  and  $\text{R}_3$  are carbides or fluorocarbons having 1 to 20 carbons,  $\text{R}_2$  is hydrogen or carbide,  $m+p$  is an integer from 1 to 30,  $n+q$  is an integer from 0 to 10, and the surfactant is about 0.01 to about 1.0 wt.% based on the total weight of the deionized water.